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PTO/SB/21 (02-04)  
 Approved for use through 07/31/2006. OMB 0651-0031  
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<b>TRANSMITTAL FORM</b> (to be used for all correspondence after initial filing)		Application Number	10/710,669
		Filing Date	07/28/2004
		First Named Inventor	Weng, Yi-Tang
		Art Unit	
		Examiner Name	
Total Number of Pages in This Submission	21	Attorney Docket Number	NANP0001USA

ENCLOSURES (Check all that apply)		
<input checked="" type="checkbox"/> Fee Transmittal Form <input type="checkbox"/> Fee Attached <input type="checkbox"/> Amendment/Reply <input type="checkbox"/> After Final <input type="checkbox"/> Affidavits/declaration(s) <input type="checkbox"/> Extension of Time Request <input type="checkbox"/> Express Abandonment Request <input checked="" type="checkbox"/> Information Disclosure Statement <input type="checkbox"/> Certified Copy of Priority Document(s) <input type="checkbox"/> Response to Missing Parts/Incomplete Application <input type="checkbox"/> Response to Missing Parts under 37 CFR 1.52 or 1.53	<input type="checkbox"/> Drawing(s) <input type="checkbox"/> Licensing-related Papers <input type="checkbox"/> Petition <input type="checkbox"/> Petition to Convert to a Provisional Application <input type="checkbox"/> Power of Attorney, Revocation <input type="checkbox"/> Change of Correspondence Address <input type="checkbox"/> Terminal Disclaimer <input type="checkbox"/> Request for Refund <input type="checkbox"/> CD, Number of CD(s) _____	<input type="checkbox"/> After Allowance communication to Technology Center (TC) <input type="checkbox"/> Appeal Communication to Board of Appeals and Interferences <input type="checkbox"/> Appeal Communication to TC (Appeal Notice, Brief, Reply Brief) <input type="checkbox"/> Proprietary Information <input type="checkbox"/> Status Letter <input type="checkbox"/> Other Enclosure(s) (please identify below):
Remarks _____		

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT	
Firm or Individual name	Winston Hsu, Reg. No.: 41,526
Signature	<i>Winston Hsu</i>
Date	9/17/2004

CERTIFICATE OF TRANSMISSION/MAILING			
I hereby certify that this correspondence is being facsimile transmitted to the USPTO or deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date shown below.			
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Signature		Date	

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PTO/SB/17 (10-03)

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# FEE TRANSMITTAL for FY 2004

Effective 10/01/2003. Patent fees are subject to annual revision.

☐ Applicant claims small entity status. See 37 CFR 1.27

TOTAL AMOUNT OF PAYMENT (\$ ) 0.00

**Complete if Known**

Application Number	10/710,669
Filing Date	07/28/2004
First Named Inventor	Weng, Yi-Tang
Examiner Name	
Art Unit	
Attorney Docket No.	NANP0001USA

**METHOD OF PAYMENT (check all that apply)**☐ Check ☐ Credit card ☐ Money Order ☐ Other ☐ None☒ Deposit Account:Deposit Account Number  
Deposit Account Name

50-3105

North America Intellectual Property Corp.

The Director is authorized to: (check all that apply)

☒ Charge fee(s) indicated below ☒ Credit any overpayments☒ Charge any additional fee(s) or any underpayment of fee(s)☐ Charge fee(s) indicated below, except for the filing fee to the above-identified deposit account.**FEE CALCULATION****1. BASIC FILING FEE**

Large Entity		Small Entity		Fee Description	Fee Paid
Fee Code	Fee (\$)	Fee Code	Fee (\$)		
1001	770	2001	385	Utility filing fee	
1002	340	2002	170	Design filing fee	
1003	530	2003	265	Plant filing fee	
1004	770	2004	385	Reissue filing fee	
1005	160	2005	80	Provisional filing fee	
SUBTOTAL (1)					(\$ ) 0.00

**2. EXTRA CLAIM FEES FOR UTILITY AND REISSUE**

		Extra Claims		Fee from below	Fee Paid
Total Claims	<input type="text"/>	-20** =	<input type="text"/>		
Independent Claims	<input type="text"/>	-3** =	<input type="text"/>	X	<input type="text"/>
Multiple Dependent					<input type="text"/>

Large Entity		Small Entity		Fee Description
Fee Code	Fee (\$)	Fee Code	Fee (\$)	
1202	18	2202	9	Claims in excess of 20
1201	86	2201	43	Independent claims in excess of 3
1203	290	2203	145	Multiple dependent claim, if not paid
1204	86	2204	43	** Reissue independent claims over original patent
1205	18	2205	9	** Reissue claims in excess of 20 and over original patent

SUBTOTAL (2) (\$ ) 0.00

\*\*or number previously paid, if greater; For Reissues, see above

**FEE CALCULATION (continued)****3. ADDITIONAL FEES**

Large Entity		Small Entity		Fee Description	Fee Paid
Fee Code	Fee (\$)	Fee Code	Fee (\$)		
1051	130	2051	65	Surcharge - late filing fee or oath	
1052	50	2052	25	Surcharge - late provisional filing fee or cover sheet	
1053	130	1053	130	Non-English specification	
1812	2,520	1812	2,520	For filing a request for <i>ex parte</i> reexamination	
1804	920*	1804	920*	Requesting publication of SIR prior to Examiner action	
1805	1,840*	1805	1,840*	Requesting publication of SIR after Examiner action	
1251	110	2251	55	Extension for reply within first month	
1252	420	2252	210	Extension for reply within second month	
1253	950	2253	475	Extension for reply within third month	
1254	1,480	2254	740	Extension for reply within fourth month	
1255	2,010	2255	1,005	Extension for reply within fifth month	
1401	330	2401	165	Notice of Appeal	
1402	330	2402	165	Filing a brief in support of an appeal	
1403	290	2403	145	Request for oral hearing	
1451	1,510	1451	1,510	Petition to institute a public use proceeding	
1452	110	2452	55	Petition to revive - unavoidable	
1453	1,330	2453	665	Petition to revive - unintentional	
1501	1,330	2501	665	Utility issue fee (or reissue)	
1502	480	2502	240	Design issue fee	
1503	640	2503	320	Plant issue fee	
1460	130	1460	130	Petitions to the Commissioner	
1807	50	1807	50	Processing fee under 37 CFR 1.17(q)	
1806	180	1806	180	Submission of Information Disclosure Stmt	
8021	40	8021	40	Recording each patent assignment per property (times number of properties)	
1809	770	2809	385	Filing a submission after final rejection (37 CFR 1.129(a))	
1810	770	2810	385	For each additional invention to be examined (37 CFR 1.129(b))	
1801	770	2801	385	Request for Continued Examination (RCE)	
1802	900	1802	900	Request for expedited examination of a design application	

Other fee (specify)

\*Reduced by Basic Filing Fee Paid

SUBTOTAL (3) (\$ ) 0.00

**SUBMITTED BY**

(Complete (if applicable))

Name (Print/Type)	Winston Hsu	Registration No. (Attorney/Agent)	41,526	Telephone	886289237350
Signature	<i>Winston Hsu</i>	Date	9/7/2004		

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**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

5 Applicants: Weng, Yi-Tang  
Filing Date: 07/28/2004  
Serial No.: 10/710,669  
Docket No.: NANP0001USA

10 Title: METHOD FOR FABRICATING A PACKAGING SUBSTRATE

To: Commissioner for Patents  
P.O. BOX 1450  
Alexandria, VA 22313-1450

15 Subject: Information disclosure statement under 37C.F.R.§1.56.

Dear Sir/Madame:

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This is an Information Disclosure Statement in accordance with the duty to disclose information material to patentability under 37 C.F.R. §1.56. The Applicant wishes to make of record the document listed on the accompanying form PTO/SB/08A. It is respectfully requested that the Examiner initials the cited reference on the form and that it be made of record in the application and that a copy of the initialed form be sent to the Applicant with the next communication from the Examiner. Since the IDS is filed before the mailing of a first Office action on the merits, a petition to request consideration of the information disclosure statement is hereby requested according to 37 CFR §1.97(b).

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To comply with 37 C.F.R.§1.98, the Applicant hereby respectfully submits a copy of the cited reference (Taiwan Patent Pub. No. 538,512), and a concise explanation of

the relevance.

Taiwan Patent Pub. No. 538,512 discloses a method for manufacturing a packaging substrate utilizing stacked photoresist during image transferring. As shown in Fig.1A, copper films 11 are first laminated on a core 10. As shown in Fig.1B, first image transfer process is carried out to form a photoresist 12 that defines a copper coating area A. As shown in Fig.1C, a copper layer 13 is then plated into the copper coating area A to form conductive wire pattern. As shown in Fig.1D, a second patterned photoresist 14 is stacked onto the photoresist 12. The second patterned photoresist 14 defines Ni/Au-plating area B of the pad 15. A Ni/Au layer 16 is then plated into the Ni/Au-plating area B, as shown in Fig.1E. Subsequently, the photoresist 12 and photoresist 14 are removed simultaneously. As shown in Fig.1G, the copper films 11 that are not covered by the formed pattern are etched away. Finally, as shown in Fig.1H, patterned solder mask is formed thereon.

As described in the Background of the specification of the present application, the prior art method disclosed in Taiwan Patent Pub. No. 538,512 encounters a Ni/Au overhang problem due to that the sidewalls of the contact pad are not covered by the Ni/Au layer (can be explicitly seen through Fig.1G~Fig.1H). The exposed sidewalls of the contact pads may be oxidized resulting in short circuiting or reliability concerns.

According to the claimed invention of the present application, a method for fabricating a packaging substrate is disclosed. A carrier plate having thereon at least one thin copper base layer is prepared. A first patterned photoresist layer is then formed on the thin copper base layer, the first patterned photoresist layer has a recessed trench area defining a copper circuit pattern. Copper is electroplated into the recessed trench area to form the copper circuit pattern. The first patterned photoresist layer is then removed. Thereafter, a second patterned photoresist layer exposing an Au-plating area of the copper circuit pattern is formed. The thin copper base layer exposed by the second patterned photoresist layer is etched away. A third patterned photoresist layer is formed on the second patterned photoresist layer to mend a recess under the second patterned photoresist layer. Using the third patterned photoresist

layer as an electroplating mask, a conventional electroplating process is performed to electroplate a metal layer onto the copper circuit pattern in the Au-plating area. The second and third patterned photoresist layers are removed. The remaining thin copper base layer being exposed after stripping the second and third patterned photoresist layers is then removed.

The present invention comprises at least the following advantages. First, the cost per substrate is reduced since there is no need to coat an additional conductive metal layer for electroplating after the definition of circuit pattern layout. The conductive materials used to assist electroplating include the thin copper base layer and the chemically deposited copper layer. The potential scratch or collision damages can be effectively prevented since the entire circuit pattern is revealed at a later fabrication stage. Further, metal peeling is avoided thereby promoting the production yield. Moreover, sidewalls of the circuit pattern in the Au-plating area are also covered by Ni/Au film and thus avoiding overhang problem.

It is therefore believed that the claimed invention of the present application is substantially different from the prior art Taiwan Patent Pub. No. 538,512. For convenience, Claim 1 of the present application is listed below:

Claim 1 A method for fabricating a packaging substrate, comprising:  
providing a carrier plate having thereon at least one thin copper base layer;  
forming a first patterned photoresist layer on said thin copper base layer, said first patterned photoresist layer has a recessed trench area defining a copper circuit pattern;  
electroplating copper in said recessed trench area to form said copper circuit pattern including a to-be-Au-plating area that has a larger surface area as the terminal of said copper circuit pattern;  
stripping said first patterned photoresist layer;  
forming a second patterned photoresist layer exposing said to-be-Au-plating area of said copper circuit pattern;  
using said second patterned photoresist layer as an etching hard mask, etching

away said thin copper base layer exposed by said second patterned photoresist layer and said to-be-Au-plating area;

forming a third patterned photoresist layer on said second patterned photoresist layer to mend a recess under said second patterned photoresist layer;

5 using said third patterned photoresist layer as an electroplating mask, electroplating a metal layer onto said copper circuit pattern in said to-be-Au-plating area;

stripping said second and third patterned photoresist layers; and

etching away remaining said thin copper base layer being exposed after stripping  
10 said second and third patterned photoresist layers.

15

Respectfully Submitted,

20 Winston Hsu  
Winston Hsu, Patent Agent No. 41,526  
P.O. BOX 506  
Merrifield, VA 22116  
U.S.A.

Date: 9/17/2004

25 e-mail : winstonhsu@naipo.com.tw

(Please contact me by e-mail if you need a telephone communication and I will return your call promptly.)